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[Signature]

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): MORIOKA, et al

Serial No.: 09/805,188

Filed: March 14, 2001

For: METHOD AND APPARATUS FOR ANALYZING THE STATE
OF GENERATION OF FOREIGN PARTICLES IN
SEMICONDUCTOR FABRICATION PROCESS

Group: 2877

Examiner: T. Nguyen

AMENDMENT

Mail Stop Fee-Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

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JUN 17 2003
TECHNOLOGY CENTER 2800

June 13, 2003

Sir:

The following amendments and remarks are respectfully submitted in
response to the Office Action dated February 13, 2003.

IN THE CLAIMS:

Please amend claims 1, 4, 6, 8, 10, 12, 15, 17, 20 and 22 as follows:

1. (amended) A processing method for semiconductor devices in a
semiconductor fabrication line, comprising the steps of:
processing a substrate in a first processing apparatus;
transferring the substrate processed in the first processing apparatus to a
detecting apparatus without removal of the substrate from the semiconductor
fabrication line while continuing fabrication of the semiconductor devices;

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